

IN THE CLAIMS:

This listing of claims replaces all prior versions of claims in the application.

Listing of Claims

1-6 Canceled

7. (New) A vacuum processing apparatus comprising:

a transfer chamber inside of which an object wafer to be processed is transferred;

two processing chambers disposed outside of the transfer chamber and attached to the transfer chamber in a detachable manner, the inside of each processing chamber being decompressed so as to process the wafer being placed therein using a plasma generated from a processing gas supplied thereto; and

two supply means for supplying the processing gas to the two processing chambers, respectively, the two supply means being disposed vertically outside of the transfer chamber and between the two processing chambers.

8. (New) The vacuum processing apparatus according to claim 7, further comprising a gas supply path that connects each of the two supply means to each of the two processing chambers.

9. (New) The vacuum processing apparatus according to claim 7 wherein one of the two supply means is disposed higher than the processing chamber to which it supplies the gas, and the other supply means is disposed lower than the processing chamber to which it supplies the gas.

10. (New) The vacuum processing apparatus according to claim 8 wherein one of the two supply means is disposed higher than the processing chamber to which it supplies the gas, and the other supply means is disposed lower than the processing chamber to which it supplies the gas.

11. (New) A vacuum processing apparatus comprising:
a transfer chamber inside of which an object wafer to be processed is transferred;
two processing chambers disposed outside of the transfer chamber and attached to the transfer chamber in a detachable manner, the inside of each processing chamber being decompressed so as to process the wafer being placed therein using a plasma generated from a processing gas supplied thereto;
a substantially rectangular storage chamber disposed below the two processing chambers and housing a power source that supplies power to the processing chambers;
and
two supply means for supplying the processing gas to the two processing chambers, respectively, the two supply means being disposed vertically outside of the transfer chamber between the two processing chambers and above the storage chamber.